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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Chen *et al.*

Examiner: Stacy Whitmore

Serial No.: 10/711,418

Art Unit: 2825

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Title: NON-DESTRUCTIVE EVALUATION OF MICROSTRUCTURE AND INTERFACE
ROUGHNESS OF ELECTRICALLY CONDUCTING LINES IN SEMICONDUCTOR
INTEGRATED CIRCUITS IN DEEP SUB-MICRON REGIME

Commissioner for Patents
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RESPONSE TO THE INTERVIEW SUMMARY OF DECEMBER 15, 2006

In response to the December 15, 2006 telephonic interview between Examiner Stacy A. Whitmore and Khoi Nguyen, the applicant's representative states that the Examiner's *Interview Summary* accurately reflects the substance of the interview.

Date: January 4, 2007

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